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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Matthew J. Breitwisch, et al.

Docket: BUR920040015US1 (17427)

Serial No.: 10/710821

Dated: June 7, 2004

Filed: 08/05/04

For: ISOLATED FULLY DEPLETED
SILICON-ON-INSULATOR REGIONS BY
SELECTIVE ETCH

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with 37 C.F.R. §§ 1.97 and 1.98, it is requested that the following reference, which is also listed on the attached Form PTO-1449, be made of record in the above-identified case.

1. M.Q. Huda, et al., "Technique for Large Elevation of Source/Drain Using Implantation Mediated Selective Etching", Electrochemical and Solid-State Letters, pp. G117-G118 (2003); and

2. Japanese Laid-Open Patent Application No. JP7007075A, filed on October 1, 1995, with English Language Translation.

CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents and Trademarks, P.O. Box 1450, Alexandria, VA 22313-1450 on

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Applicants are submitting copies of the cited references, along with an English Abstract which explains the pertinence of the reference.

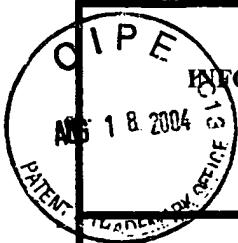
Inasmuch as this Information Disclosure Statement is being submitted in accordance with the schedule set out in 37 C.F.R. § 1.97(b), no petition, certification or fee is required.

Respectfully submitted,

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INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)

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Docket Number (Optional)

Application Number

Applicant(s)

Matthew J. Breitwisch, et al.

Filing Date

08/05/04

Group Art Uni

Unassigned

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	JP7007075A	10/1/95	Japan				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		M.Q. Huda, et al., "Technique for Large Elevation of Source/Drain Using Implantation Mediated Selective Etching", <u>Electrochemical and Solid-State Letters</u> , pp. G117-G118 (2003).

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.